

FORM PTO-1449 (SUBSTITUTE)

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEINFORMATION DISCLOSURE  
STATEMENT BY APPLICANT  
(37 CFR 1.98(b))Attorney Docket No.:  
P2001,0368Applic. No.  
10/724,903

Applicant



Grit Schwalbe et al.

Filing Date  
December 1, 2003

Group Art Unit

2823



## U.S. PATENT DOCUMENTS

EXAMINER INITIALS		PATENT NO.	DATE	PATENTEE	CLASS	SUB CLASS	FILING DATE
	A	5,168,334	12/01/92	Mitchell et al.	—	—	
	B	5,768,192	06/16/98	Eitan	—	—	
	C	5,815,433	09/29/98	Takeuchi	—	—	
	D	5,915,203	06/22/99	Sengupta et al.	—	—	
	E	5,963,465	10/05/99	Eitan	—	—	
	F	5,966,603	10/12/99	Eitan	—	—	
	G	6,133,095	10/17/00	Eitan et al.	—	—	
	H						
	I						

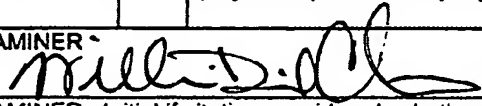
## FOREIGN PATENT DOCUMENT

		DOCUMENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	TRANSL. YES   NO
	J						
	K						
	L						
	M						
	N						

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

	O	Takhyun Yoon et al.: "A New Process Integration - P <sup>3</sup> (Pre Poly Plug) - for Giga Bit DRAM Era", <i>Symposium on VLSI Technical Digest</i> , August 1999, 2 pgs.
	P	Jong-Wan Jung et al.: "A fully working 0.14µm DRAM technology with polymetal (W/WNx/Poly-Si) gate", <i>IEEE</i> , 2000, 4 pgs.

EXAMINER



DATE CONSIDERED

3/25/2005

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609;  
Draw line through citation if not in conformance and not considered. Include copy of this form with  
next communication to applicant.